

 $D_n(E), D_n(E) = f_n(E), f_n(E) = n(E), p(E)$

E

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Minimatrix X-ray irradiations and

new dosimetry at the x-ray facility

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Why x-ray irradiations?



- SuperBelle: There will be high synchrotron radiation at the interaction point (~1 Mrad/a = 10 kGy/a)
- Simulate this ionizing radiation with x-rays
- DEPFET: Electron/Holepairs are generated in the oxide
- Trapped holes remain there for a long time
 - Change of electrical characteristics



Setup and DAQ





- Study with a 6x16 Minimatrix
- Important contacts on PCB → easy accessibility
- Drain contact needed probe needle
- Several irradiation and measurement steps
- Readout duration of input characteristic of all 96 pixels
 - $\sim 6...7h$
 - → min. 4 days of room temperature annealing
- DAQ via LabVIEW: Sweep of Gate voltage, Drain current is measured



Results of input characteristics





Change of threshold voltage



Homogeneity of the Minimatrix

Threshold voltage – Unirradiated (scale: 0.4V...1.0V)

Threshold voltage at 3.31 kGy (scale: -6.6V...-6.1V)



 \rightarrow Fluctuations are not severe



Change of gain gm



- Input characteristic curve fitted with
 - $I = aU^2 + bU + c$
 - Gain $g_m = mU + b$ via dI/dU $\rightarrow m = 2a$
 - ➔ no numeric deviation
 - Gain evaluated at Drain current = $50 \,\mu A$
- Maybe effect is part of setup and readout process → needs to be rechecked to find out if effect still occurs

Conclusions

- Threshold shift is high (~15 V at 23 kGy), but Switcher 4 should handle it
- Tests on thinner oxides (Minimatrix 180 nm) show much smaller shift, maybe Switcher 3 can do the job
- Homogeneity of threshold voltage shouldn't be a problem, though inhomogeneous irradiation at SuperBelle may prove difficult
- Change of gain may be a problem for clusterfinding (difference about 20 %) at 1.4 kGy. Should be rechecked





New dosimetry at the x-ray facility Karlsruhe

Using a GEANT4 simulated energy spectrum of a tungsten anode by Oksana Brovchenko











Determining dose rate in Silicon



- Dose rate measurement via depleted diode
- Measuring of reverse-current
- X-ray photons generate electron/hole-pairs in Si-Bulk
 - Every charge carrier pair represents an energy of 3.6 eV
 - With the x-ray generated current one gets the deposited power, with the mass of the diode → dose rate in Si



Making use of the spectrum

- Spectrum of tungsten anode (including a 0.4 mm Be filtering, black)
- Generate via absorption function of Zr a new transmitted spectrum (red)



Calibrate silicon spectrum with power measurement in diode



- Simulated Spectrum (red) hits simulated silicon of 300 µm thickness (thickness of diode)
- Calculate arbitrary power $P_{rel_{Si}} = \int N_{abs_{Si}} \cdot E \cdot dE$
- Simulated power is linked to the measured power via

$$P_{Si} = \alpha \cdot P_{rel_{Si}}$$



Calibrate SiO_2 spectrum



• Same calculation for SiO_2 spectrum (green) as for Si (blue) $P_{rel_{SiO_2}} = \int N_{abs_{SiO_2}} \cdot E \cdot dE$ Dose rate of Si spectrum is known, so the SiO₂ spectrum can be calibrated



New dose rates

- Every dose rate matches to a specific set of parameters, we assume
 - U=60 kV (max. tube voltage)
 - I=33 mA (max. tube current)
 - Distance is 155 mm $(\dot{D} \propto \frac{1}{2})$ [total distance to electron' spot on anode is 155mm + 25mm = 180mm, but distance (155mm) can easily be measured in lead container
- Dose rate in silicon $(300 \,\mu\text{m})$ $\dot{D}_{Si} \mid_{60kv,33mA,155mm,300\mu m} = 0,305 \frac{Gy}{s}$ • Dose rate in silicon dioxide (180 nm) $\dot{D}_{SiO_2} \mid_{60kV,33mA,155mm,180nm} = 0,239 \frac{Gy}{G}$

Correct old dose rates by factor 0.47

Uncertainty on dose rates

- To check it, we need to measure the spectrum... (Equipment should come any time now...)
- Until then: Use other filters
 - 1. X-ray facility has 6 kinds of filters (Zr, Fe, Mn, ...), which are easy to install
 - Check power by all filters with diode 2.
 - 3. Simulate power by all filters
 - Compare measured results, like Zr/Fe 4.
 - Compare simulated results, e. g. Zr/Fe 5.
- Q: Did the relations in step 4 and 5 match? A: Yes, to 2.3 $\% \pm 12.6 \%$. So roughly 15 % uncertainty







Acknoledgements

Thank you for listening

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Thanks also to Oksana Brovchenko for her simulated spectrum





Backupslides

03.05.2009





Different Filters - Vanadium



Different Filters - Iron



Different Filters - Mangan



Different Filters - Nickel



Measurement and Simulation (I)

Data	Signalstrom	Simulation	
Filtertyp	in nA	in a. u.	
Zr	85,2	622,537	
Ni	$268,\!4$	2579,98	
Mn	242,7	2221	
\mathbf{V}	448,5	3560,17	
Fe	309	2790,75	

Measurement					
	Zr	Ni	Mn	V	Fe
Zr	100,00	315,02	284,86	526,41	362,68
Ni	31,74	100,00	90,42	167,10	115,13
Mn	35,11	110,59	100,00	184,80	127,32
V	19,00	59,84	54,11	100,00	68,90
Fe	27,57	86,86	78,54	145,15	100,00





Measurement and Simulation (II)

Simulation	Zr	Ni	Mn	V	Fe
Zr	100,00	414,43	356,77	571,88	448,29
Ni	24,13	100,00	86,09	137,99	108,17
Mn	28,03	116,16	100,00	160,30	125,65
V	17,49	72,47	62,38	100,00	78,39
Fe	22,31	92,45	79,58	127,57	100,00
Match	Zr	Ni	Mn	V	Fe
Match Zr	Zr 0,00	Ni 31,56	Mn 25,24	V 8,64	Fe 23,61
Match Zr Ni	Zr 0,00 -23,99	Ni 31,56 0,00	Mn 25,24 -4,80	V 8,64 -17,42	Fe 23,61 -6,04
Match Zr Ni Mn	Zr 0,00 -23,99 -20,16	Ni 31,56 0,00 5,04	Mn 25,24 -4,80 0,00	V 8,64 -17,42 -13,26	Fe 23,61 -6,04 -1,31
Match Zr Ni Mn V	Zr 0,00 -23,99 -20,16 -7,95	Ni 31,56 0,00 5,04 21,09	Mn 25,24 -4,80 0,00 15,28	V 8,64 -17,42 -13,26 0,00	Fe 23,61 -6,04 -1,31 13,78

